

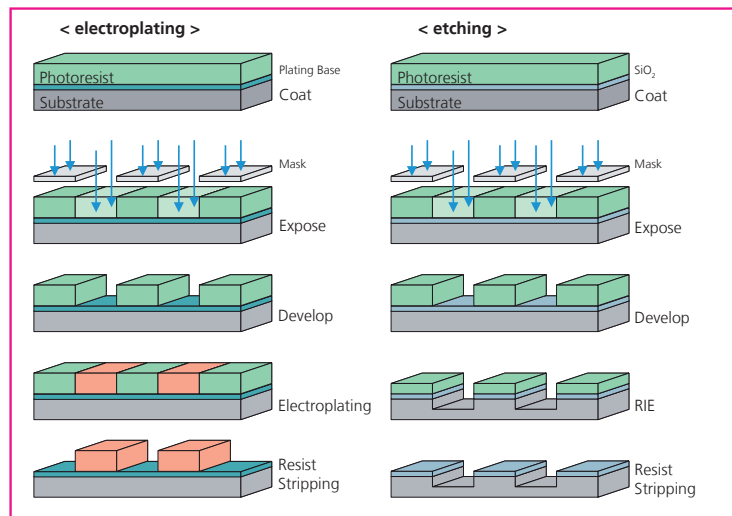
ma-P 1275 and ma-P 1275 HV – Positive Tone Photoresists

Versatile high viscosity positive tone photoresists for microsystems technology

Characteristics

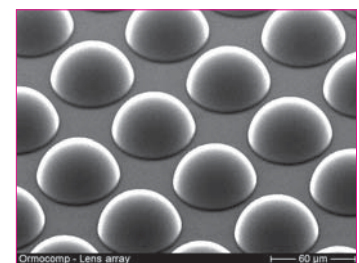
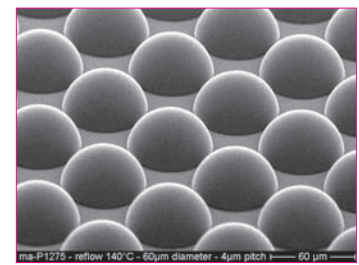
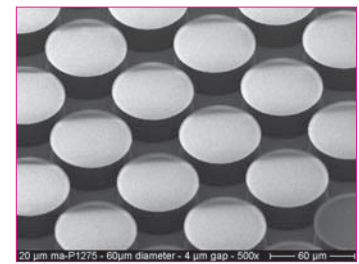
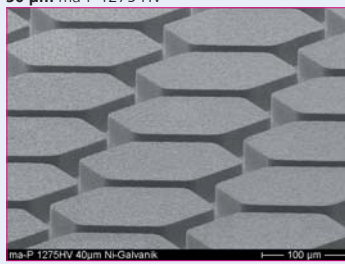
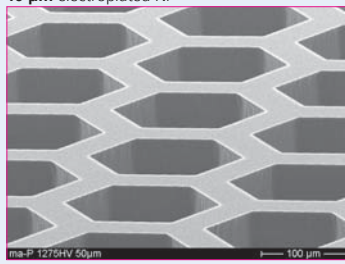
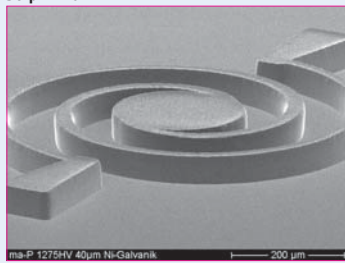
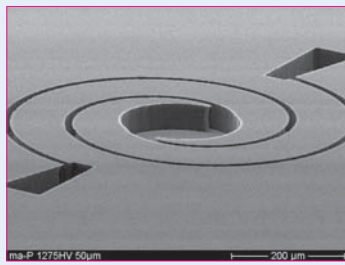
- Specifically designed for electroplating of structures in microsystems technology
- High stability in acid and alkaline plating baths
- Well suitable also for the use as an etch mask exhibiting high dry and wet etch resistance
- Good thermal stability of the resist patterns attainable
- Aqueous alkaline development
- Easy removal
- Side wall angle up to 87° with mask aligner broadband exposure

Process flow



Applications

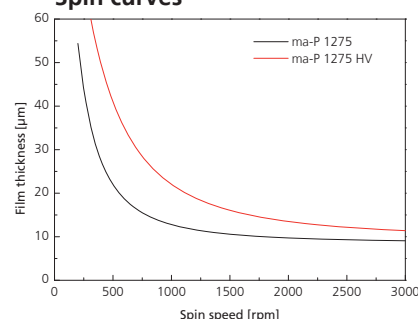
- Mould for electroplating – e.g. for micro coils, micro springs, micro optical components
- Etch mask for metal and semiconductor substrates – e.g. microlenses from reflowed patterns
- Mask for ion implantation



Film thicknesses

Film thick-ness	µm	7.5	11	20	30	40	50
ma-P 1275	rpm	3000		500	350	250	—
	s	30		60	60	60	
ma-P 1275 HV	rpm	—	3000	1100	700	500	400
	s		30	60	60	60	60

Spin curves



UV/vis spectra

